

# Epitaxial Growth of $\alpha$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> by Suboxide Molecular Beam Epitaxy on A-Plane Sapphire

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## Introduction

Alloying  $\alpha$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> creates a material with a tunable ultrawide bandgap ranging from 5.3 - 8.5 eV. This is much higher than other semiconductors including Ga<sub>2</sub>O<sub>3</sub>.

## Benefits of using Suboxide MBE

- Using suboxide MBE skips the growth rate-limiting reaction step.
- Suboxide MBE has drastically increased the growth rate of  $\alpha$ -Ga<sub>2</sub>O<sub>3</sub>.<sup>[1]</sup> Hopefully, it will do the same for  $\alpha$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub>.

## Experimental Goals

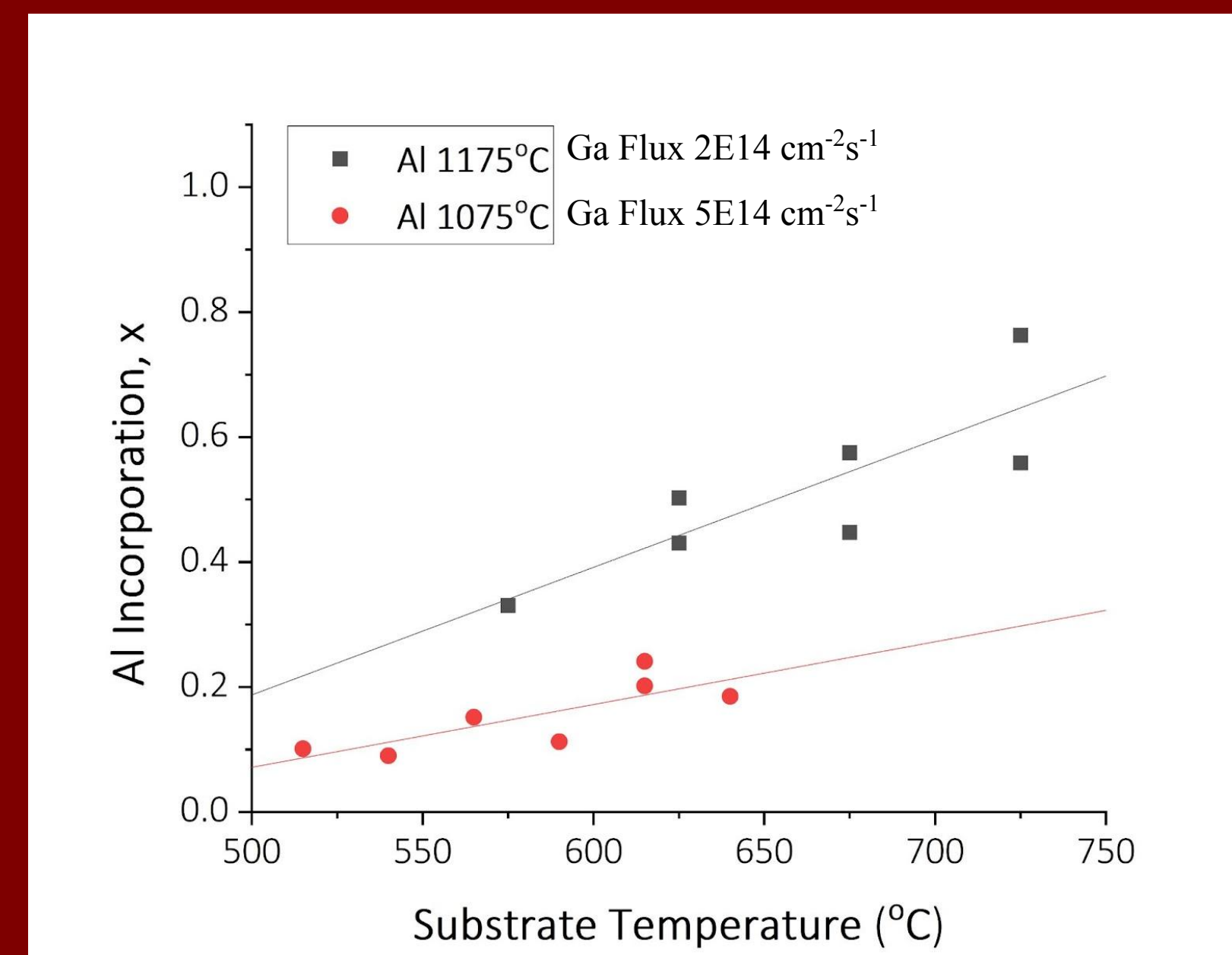
- To grow films containing = 0% to 100% Aluminum.
- To achieve a growth rate of one  $\mu\text{m/hr}$ .

## Experimental Methods

- MBE growth was achieved using Al, Ga<sub>2</sub>O, and 80% distilled ozone sources.
- Al flux and ozone pressure were constant while Ga<sub>2</sub>O flux was varied.
- All films were grown on A-plane sapphire substrates, with growth temperatures between 575 - 725 °C.

## Results

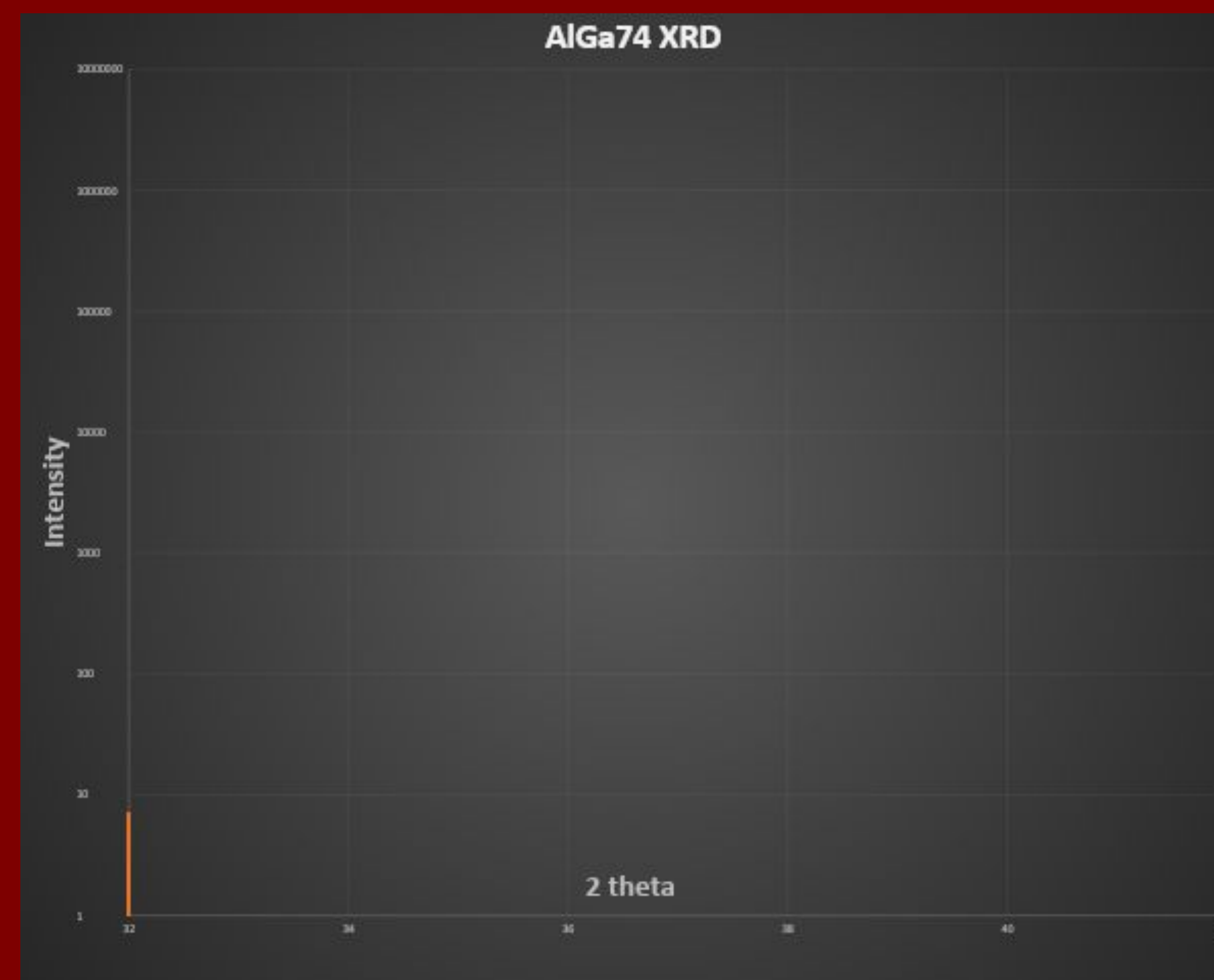
### Effects of changing temperature



Decreasing either the substrate temperature or the aluminum flux lowers the aluminum incorporation.

Steck, Jacob. Epitaxial Growth of  $\alpha$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> by Suboxide Molecular Beam Epitaxy. 8/8/2022. Cornell University

### Calculating Aluminum incorporation



The aluminum incorporation was calculated using data collected from the XRD graphs and Vegard's law.<sup>[2]</sup>

## Conclusions

Suboxide MBE is an effective way of growing epitaxial  $\alpha$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub>. By changing ozone pressure, substrate temperature, and/or relative fluxes, x can be tuned to anywhere within the range of 0-0.98. Growing at higher distilled ozone pressures allows for growth of high quality films with rates of over 1  $\mu\text{m/hr}$ .

## References

1. Vogt, Patrick et al (2020). Adsorption-Controlled Growth of Ga<sub>2</sub>O<sub>3</sub> by Suboxide Molecular-Beam Epitaxy.
2. R. Jinno, et al. Sci Adv. 7, eabd5891, (2021).

## Acknowledgements

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